

Mechanical Behavior and Active Deformation Mechanisms in Thin Film Mg

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Background & Motivation



- Interest in Mg has gained traction for application in
 - Light weight structural alloys, low density but pure Mg relatively weak
 - Hydrogen storage (metal hydrides) for alternative energy
- Possible improvements from length scale reduction
 - Small grains → Hall-Petch strengthening
 - Small thickness → Shorter pathways for improved diffusion

KEY QUESTIONS

- How do small grains affect the mechanical properties of Mg?
- What deformation mechanisms are active?

Film Synthesis & Testing

Fabrication Flow

Nitride



(1) Double side polish $<100>$ Si wafer w/ nitride



(2) Open window on backside to expose Si



(3) Etch from backside w/ KOH; thin window



(4) Pattern resist on frontside w/ tensile geometry



(5) Physical vapor deposition of thin film



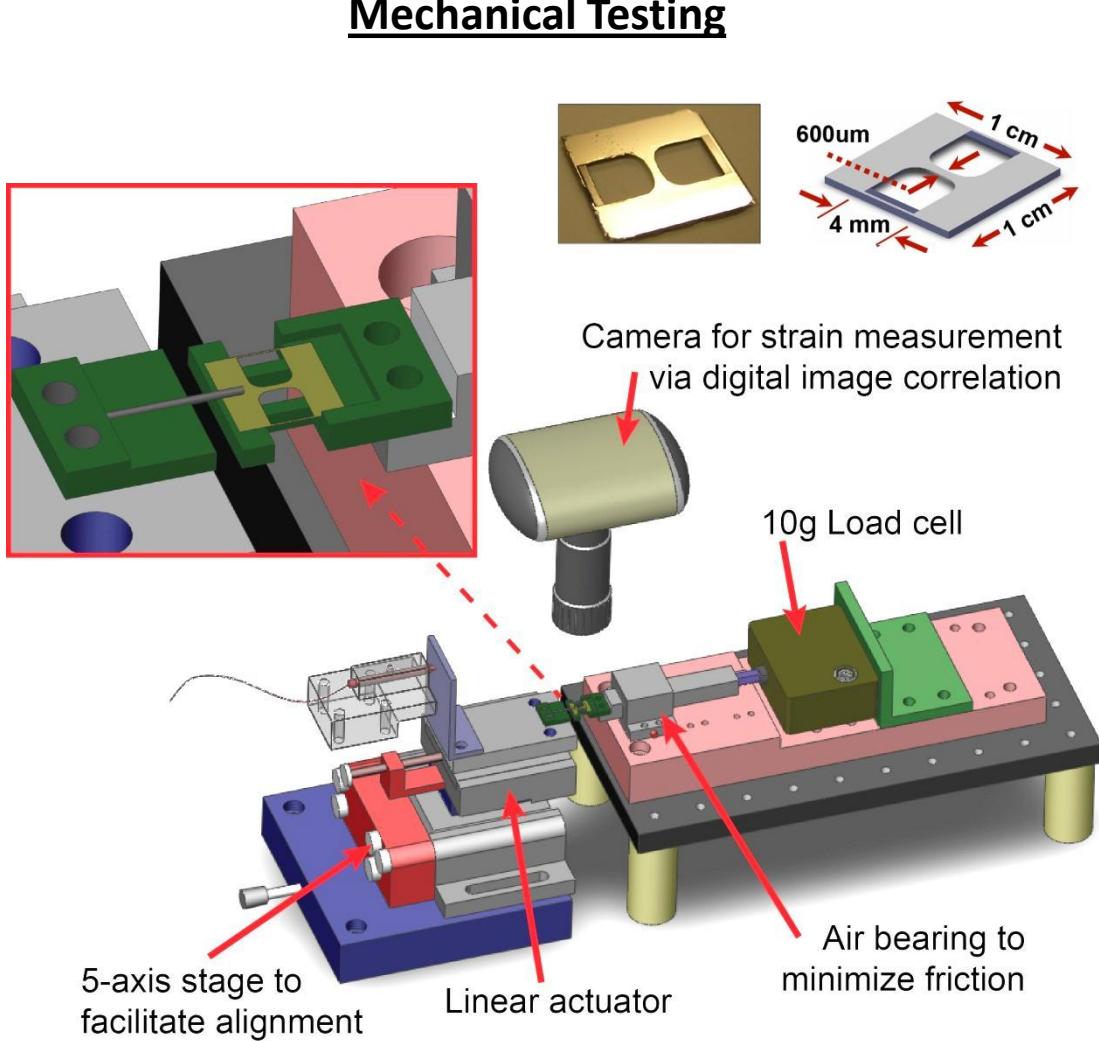
(6) Lift-off, remove resist + extraneous metal



(7) Remove Si under gauge w/ XeF2



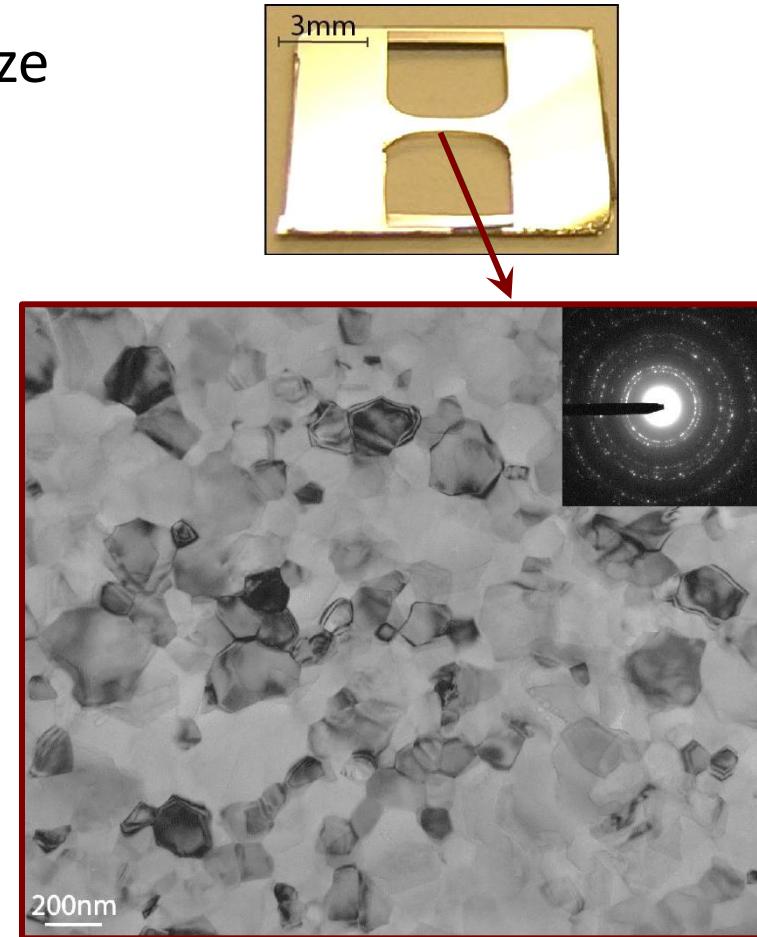
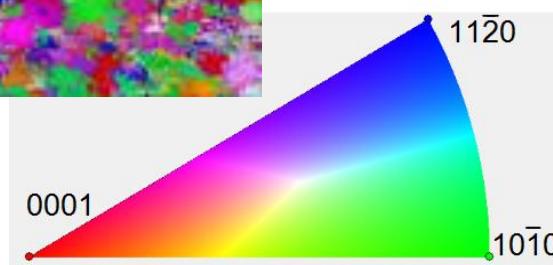
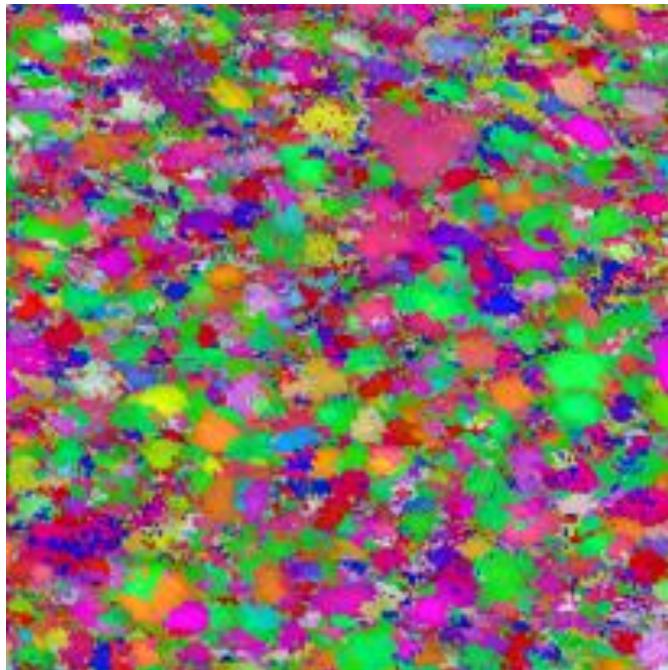
Mechanical Testing



D.S. Gianola, et. al ; TMS Letters; 1 (2004)

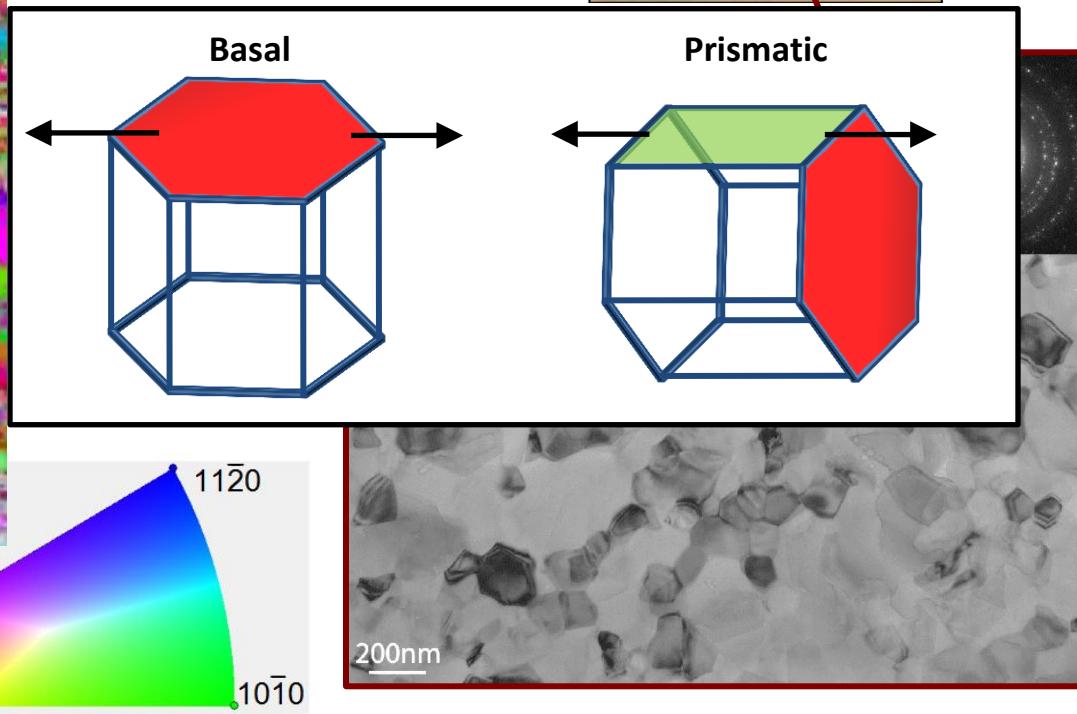
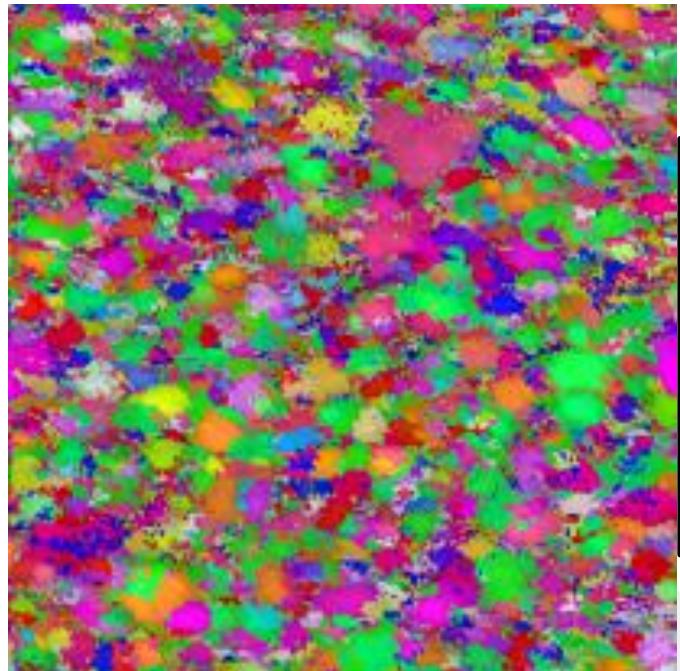
As-deposited Test Specimens

- 250nm thick films, 99.999% pure Mg e-beam evaporated under a base pressure of 8×10^{-7} Torr
- Dislocation free grains, 197nm in size

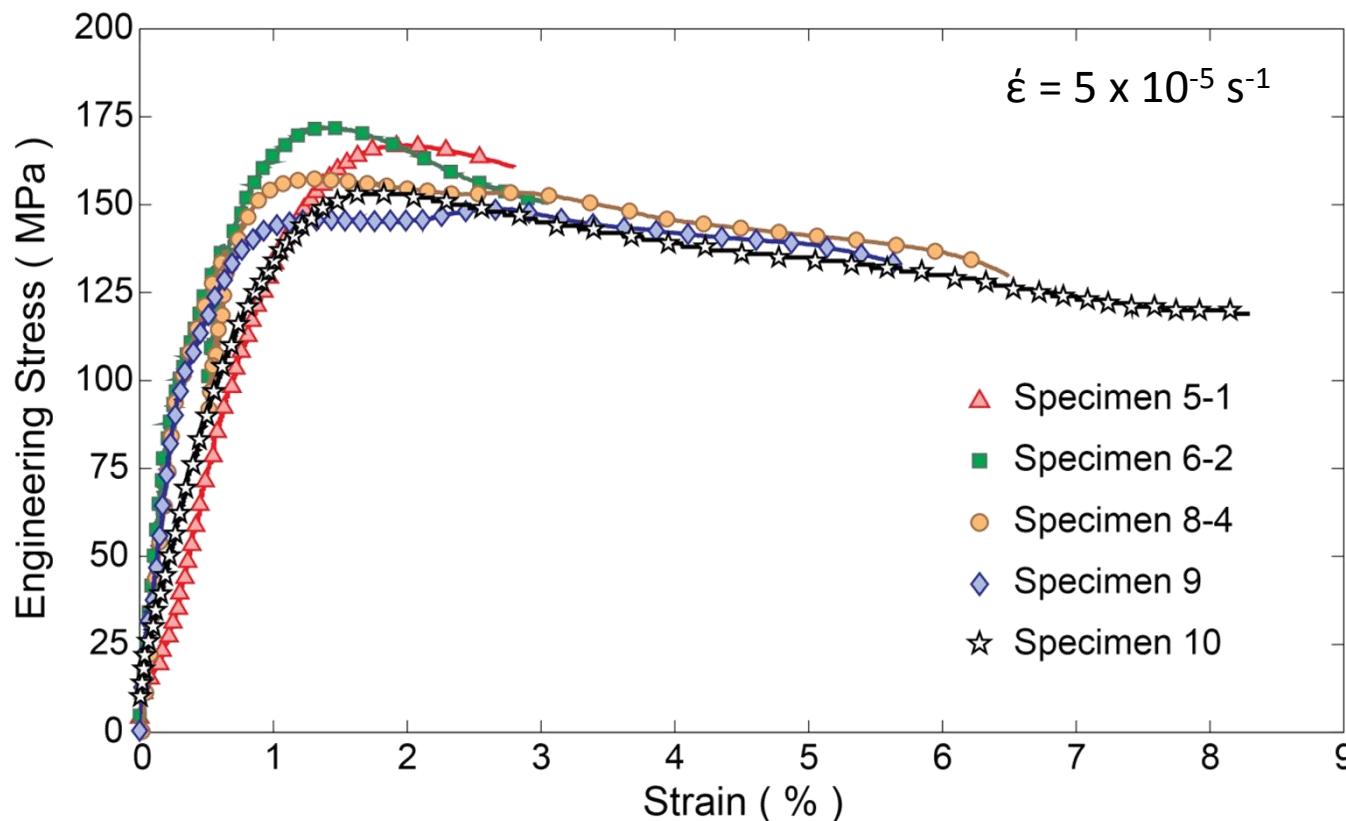


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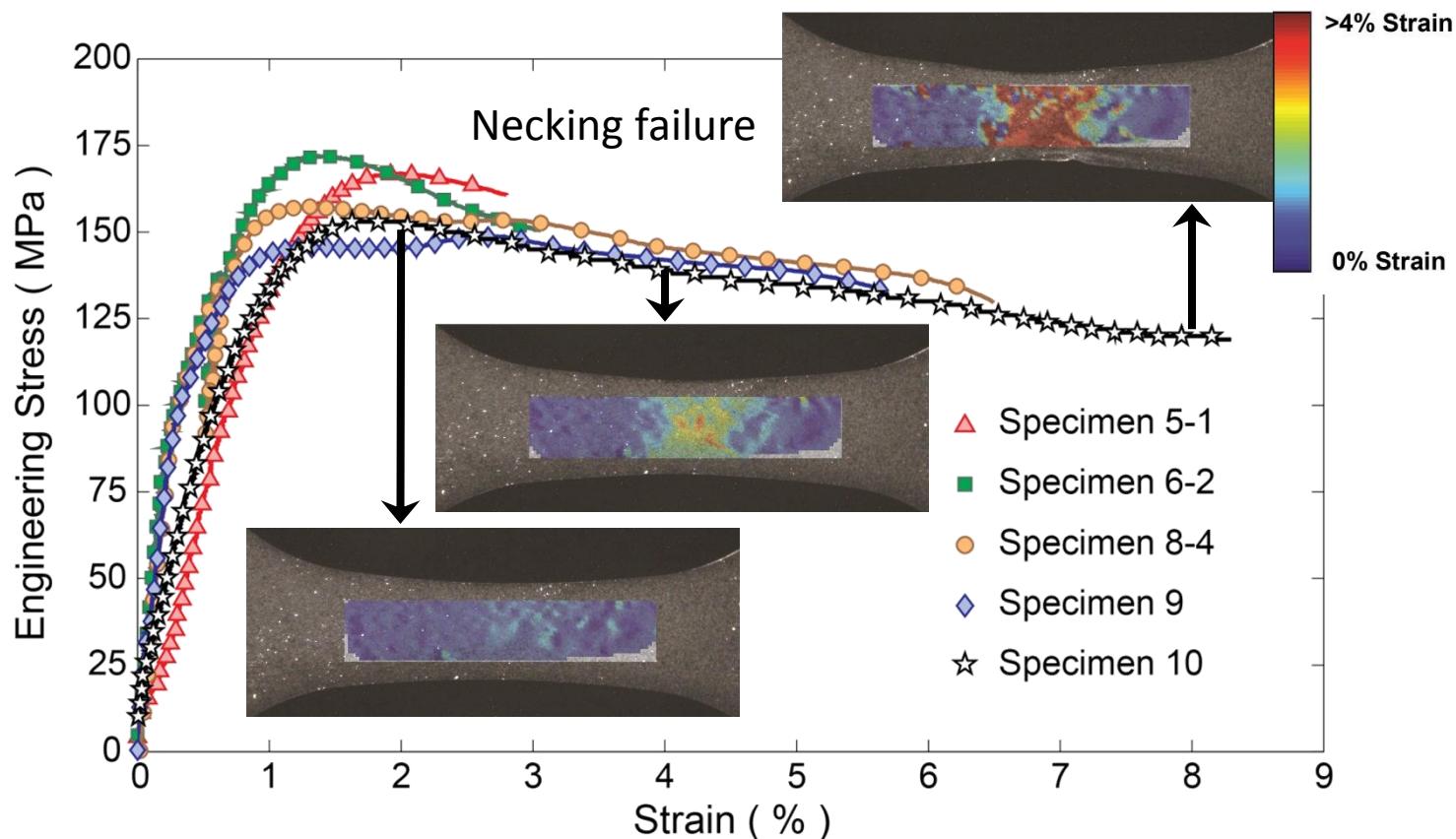


Mechanical Response



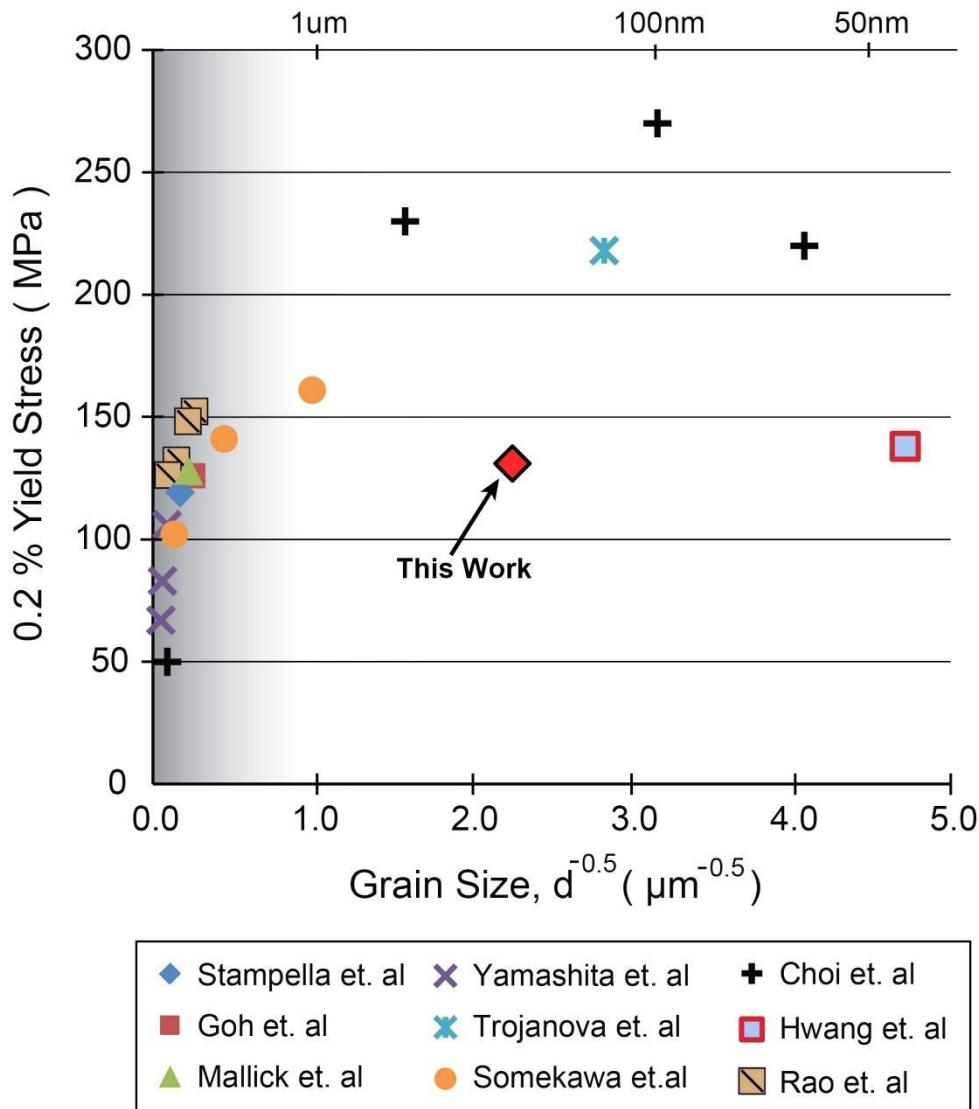
- Response similar to coarse grained Mg
 - Strengths of 160-195 MPa and elongations of 3 – 15%

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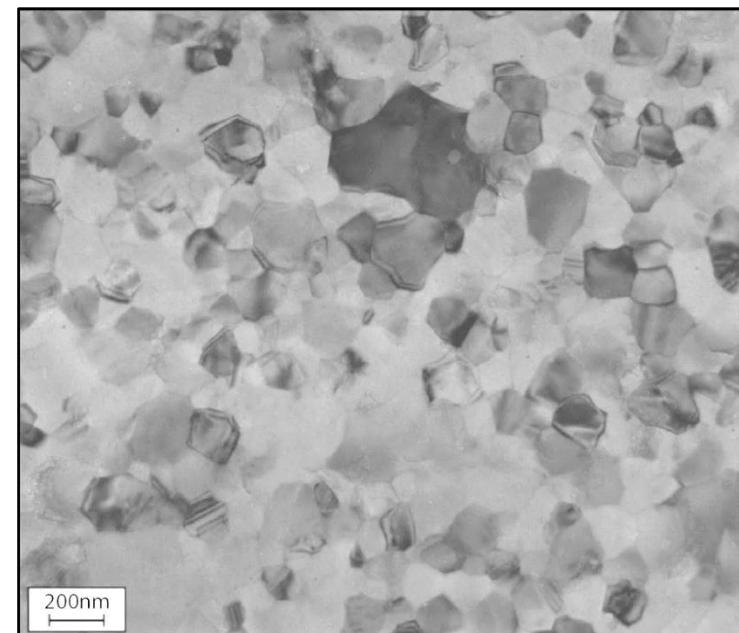
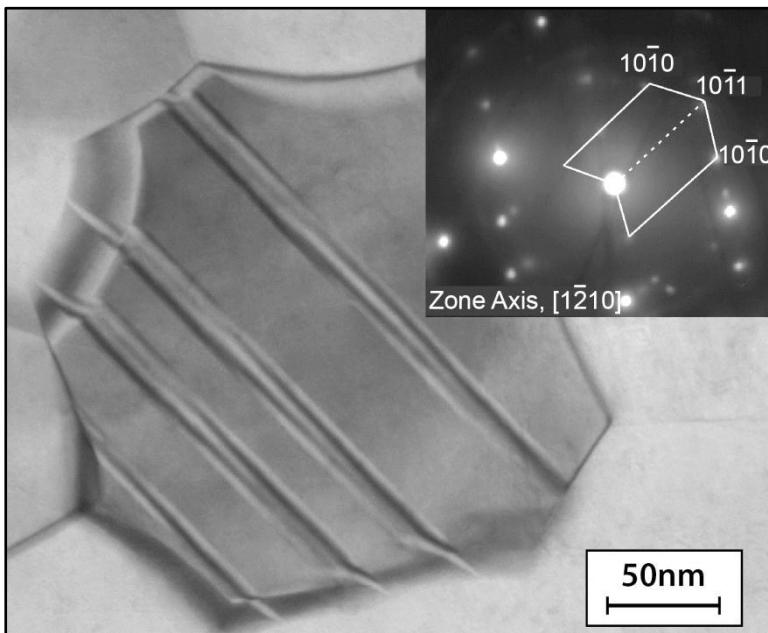
Strengthening ?



- “Bulk” yield point for the Mg films of this study
- Yield stress affected by
 - Purity
 - Texture
 - Processing
- Differences in these factors preclude a direct comparison of all data

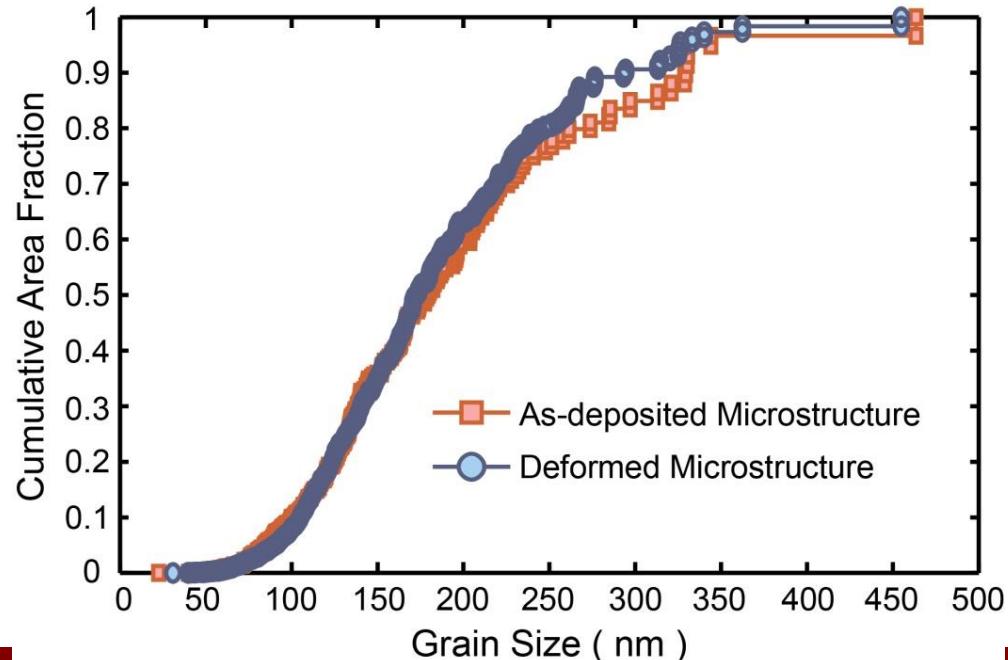
Deformation Mechanisms

- No storage of dislocations
 - Possible nucleation & absorption of dislocations at GBs
- $\{10\bar{1}1\} <10\bar{1}2>$ twins
 - Deformation twins on pyramidal plane, bulk like yielding not likely from this twin system as Basal, τ_{crss} < Prismatic, τ_{crss} < Pyramidal, τ_{crss}



Deformation Mechanisms

- No change in the grain size, no extensive GB migration or rotation events
- GS distribution reveals many grains \approx film thickness,
 - Grains with $<10\bar{1}1>$ normal to film surface would have ~ 50 MPa of resolved shear on basal plane (Basal, $\tau_{\text{crss}} = 0.77$ MPa)
 - Yielding of such unconstrained grains will manifest on stress-strain response



Summary

- At 200nm GS, twinning is active with a lack of dislocation pile up
- “Bulk” yield point stems from yielding of grains spanning the full film thickness

Future Work

- In-situ TEM experiments to determine extent of dislocation and GB related processes
- Explore impact of purity and oxide on strength